## AMENDMENT

## IN THE CLAIMS:

Please amend the claims as follows:

 (Currently amended) A two-fluid nozzle for cleaning substrates which mixes gas and liquid internally and injects liquid droplets with gas so as to clean a substrate, comprising:

a gas supply passage for supplying gas, a liquid supply passage for supplying liquid, and a lead-out passage for leading out internally-formed liquid droplets,

wherein an injection port for injecting liquid droplets to the outside is formed at the front end of said lead-out passage, and

wherein a cross-sectional area Sb of said injection port is formed smaller than a crosssectional area Sa of said lead-out passage, and a cross-sectional area Sc of an exit of said gas
supply passage is formed smaller than the cross-sectional area Sa of said lead-out passage, and
wherein said lead-out passage is formed in a straight shape, and the cross-sectional area
Sb of said injection port is formed constant from an entrance thereof to an exit thereof.

2. (Original) The two-fluid nozzle for cleaning substrates as set forth in claim 1.

wherein a ratio Sa: Sb between the cross-sectional area Sa of said lead-out passage and the cross-sectional area Sb of said injection port is 1:0.25 to 0.81.

3. (Original) The two-fluid nozzle for cleaning substrates as set forth in claim 1,

wherein the cross-sectional area Sc of the exit of said gas supply passage is formed equal to the cross-sectional area Sb of said injection port or smaller than the cross-sectional area Sb of said injection port.

4. (Original) The two-fluid nozzle for cleaning substrates as set forth in claim 3,

wherein a ratio Sb: Sc between the cross-sectional area Sb of said injection port and the cross-sectional area Sc of the exit of said gas supply passage is 1: 0.16 to 0.87.

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- 5. (Original) The two-fluid nozzle for cleaning substrates as set forth in claim 4, wherein the cross-sectional area Sc of the exit of said gas supply passage is 1.13 mm<sup>2</sup> to 6.16 mm<sup>2</sup>.
- 6. (Original) The two-fluid nozzle for cleaning substrates as set forth in claim 4, wherein the cross-sectional area Sc of the exit of said gas supply passage is 1.77 mm² to 4.91 mm²
- 7. (Original) The two-fluid nozzle for cleaning substrates as set forth in claim 1, wherein said lead-out passage is formed in a straight shape, and the cross-sectional area Sa of Said lead-out passage is constant.
- (Original) The two-fluid nozzle for cleaning substrates as set forth in claim 1, wherein a length L1 of said lead-out passage is 10 mm to 90 mm.
- (Original) The two-fluid nozzle for cleaning substrates as set forth in claim 1, wherein a length L2 of said injection port is 30 mm or shorter.
- 10. (Original) The two-fluid nozzle for cleaning substrates as set forth in claim 1, comprising a liquid introduction passage in an annular shape surrounding said gas supply passage, and having a structure such that

said gas supply passage is arranged coaxially with said lead-out passage, said liquid supply passage is opened on an outer peripheral face of said liquid introduction passage,

a taper portion is formed with a diameter which gets smaller toward a front end side in said liquid introduction passage,

the taper portion is opened between said gas supply passage and said lead-out passage, and

gas supplied from said gas supply passage and liquid introduced from said liquid

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introduction passage are mixed to form liquid droplets and the liquid droplets are lead out via said lead-out passage.

11. (Original) The two-fluid nozzle for cleaning substrates as set forth in claim 1, wherein said injection port is formed with a vertical cross-sectional shape of an exit side periphery having a right angle or an acute angle.

- 12. (Original) A substrate cleaning apparatus, comprising:
  - a two-fluid nozzle for cleaning substrates as set forth in claim 1;
  - a spin chuck for holding a substrate substantially horizontally; and
- a drive mechanism for moving said two-fluid nozzle for cleaning substrates above the substrate.